NANO
LETTERS

2009
Vol. 9, No. 2
919

# Additions and Corrections

Vol. 9, 2009

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Electrostatic Force Assisted Exfoliation of Prepatterned Few-Layer Graphenes into Device Sites.

Page 467. Our recent publication[1] overlooked and in part replicated earlier work on electrostatic deposition of graphene by Sidorov et al.[2] In our letter, we reported on using a combination of electrostatic exfoliation with micro- and nanolithographically patterned HOPG to fabricate graphene-based devices over large areas with sub-20 nm patterning and placement resolution that we claim as important novelty in the paper. However, the electrostatic deposition of unpatterned graphene with the ability to control the number of graphene layers by Sidorov et al.[2] predates our work. Additional applications and extensions of the electrostatic exfoliation method for controlling the number of graphene layers and creating graphene air-bridges[3] and rolled graphene[4] have also been reported.

**Acknowledgment.** We thank the University of Louisville authors for bringing their reports to our attention and apologize for overlooking their contributions in our letter.

**References**

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NL803860X

10.1021/nl803860x
**Published on Web 01/13/2009**

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